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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Nobuo SHIMAZU et al.

Serial No : 09/765,388

Filed : January 22, 2001

For : ELECTRON BEAM PROXIMITY
EXPOSURE APPARATUS AND METHOD

Examiner: Unknown

Art Unit: Unknown

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 20231, on July 2, 2001.

K.M. McManus
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PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

Dear Sir:

Preliminary to calculation of the filing fee and examination of this application, please enter the following amendments:

IN THE SPECIFICATION:

Please amend the specification as follows. Attached herewith is a marked-up version of the amended paragraphs.

Page 8, lines 17-23:

Figs. 6(A) and 6(B) are views showing portions of an electron gun 14, the condenser lens 18 and the blanker electrodes 66 in the electron beam proximity exposure apparatus according to the embodiment. Fig. 6(A) is a sectional view including the optical axis (the Z-axis) and the X-axis, and Fig. 6(B) is a sectional view including the Z-axis and the Y-axis. Here the blanker electrodes 66 comprise two electrodes parallel disposed. When voltage is applied, the blanker electrodes 66 form an electric field in the Y-axis direction and no electric field in the direction of the X-axis.

Page 10, lines 5-14: